PATENT

Attorney Docket: 207,587

## **IN THE CLAIMS:**

[1.] 1. (Currently Amended) A base pad of a chemical mechanical polishing pad, which does not include fine pores and has a hardness of 10-100 Shore D and compressibility of 1-10%.

wherein the base pad is produced in such a manner that at least one compound is selected from the group consisting of polyurethane, PVC, polyvinyl alcohol, polyacrylic acid, polyacrylamide, polyethylene oxide, maleic acid copolymer, methylcellulose, and carboxymethylcellulose, is reacted in a first reactor to first produce a prepolymer, and

the prepolymer is reacted with a substance having a polyol reaction group or an ammonia reaction group in a weight ratio of 3:1-2:1 in a second step so as to achieve complete hardening.

- [2.] 2. (Original) The base pad as set forth in claim 1, wherein the base pad is 500-2500 micrometers in thickness.
  - 3. (Cancelled)
  - 4. (Cancelled)
- [5.] 5. (Currently Amended) A multilayer polishing pad which is produced using a base pad including no fine pores and having hardness of 10-100 Shore D and compressibility of 1-10%,

wherein the base pad is produced in such a manner that at least one compound selected from the group consisting of polyurethane, PVC, polyvinyl alcohol, polyacrylic acid, polyacrylamide, polyethylene oxide, maleic acid copolymer, methylcellulose, and carboxymethylcellulose, is reacted in a first reactor to first produce a prepolymer, and

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the prepolymer is reacted with a substance having a polyol reaction group or an ammonia reaction group in a weight ratio of 3:1-2:1 in a second step so as to achieve complete hardening.

- [6.] 6. (Currently Amended) The multilayer polishing pad as set forth in claim 5, comprising a polishing pad having a polishing layer for polishing, and a base pad for supporting the polishing pad.
- [7.] 7. (Currently Amended) The multilayer polishing pad as set forth in claim 5, wherein the multilayer polishing pad has a thickness of 2000-4000 micrometers, in which the base pad has a thickness of 500-2500 micrometers.
  - 8. (Cancelled)
  - 9. (Cancelled)